EXPLANATION OF REFERENCE

101: LASER OSCILLATOR, 102: SLIT, 103: MIRROR, 104: BEAM, 105: CONVEX CYLINDRICAL LENS, 106: CONVEX CYLINDRICAL LENS, 107: SUBSTRATE, 108: SUCTION STAGE, 109: X STAGE, 110: Y STAGE, 301: SLIT OPENING PORTION, 302: BLOCKING PLATE, 401: LASER, 402: LASER, 403: HALF-WAVEPLATE, 404: POLARIZING BEAM SPLITTER, 405: SLIT, 406: MIRROR, 407: MIRROR, 408: CONVEX CYLINDRICAL LENS, 409: CONVEX CYLINDRICAL LENS, 410: SEMICONDUCTOR FILM, 411: X STAGE, 412: Y STAGE, 501: SEMICONDUCTOR FILM, 502: LARGE CRYSTAL GRAIN REGION, 600: LOWER ELECTRODE, 601: FIRST SUBSTRATE, 602: METAL FILM, 603: METAL OXIDE FILM, 604: SILICON OXIDE FILM, 605: CONDUCTIVE FILM, 700: INSULATING FILM, 701: FIRST GATE INSULATING FILM, 701a: SILICON NITRIDE OXIDE FILM, 701b: SILICON OXYNITRIDE FILM, 702a: NON-SINGLE CRYSTAL SEMICONDUCTOR FILM, 702b: CRYSTALLINE SEMICONDUCTOR FILM, 703: SECOND GATE INSULATING FILM, 704: UPPER ELECTRODE, 704a: CONDUCTIVE FILM, 704b: CONDUCTIVE FILM, 705: RESIST MASK, 706: IMPURITY REGION, 707: SECOND CONDUCTIVE FILM, 900: LDD REGION, 901: INSULATING FILM, 902: INTERLAYER INSULATING FILM, 903: WIRING, 1000: SUBSTRATE, 1001: BASE FILM, 1002: NON-SINGLE CRYSTAL SEMICONDUCTOR FILM, 1003: LASER, 1004: CYLINDRICAL LENS, 1005: CYLINDRICAL LENS, 1006: CRYSTALLINE SEMICONDUCTOR FILM, 1007: SEMICONDUCTOR FILM, 1008: GATE INSULATING FILM, 1101: RESIST, 1102: CONDUCTIVE FILM, 1102a: FIRST CONDUCTIVE FILM, 1103: RESIST MASK,

1103a: RESIST MASK, 1003b: RESIST MASK, 1201: GATE ELECTRODE, 1301:

SOURCE REGION, 1302: LOW-CONCENTRATION IMPURITY REGION, 1303:

REGION WHERE LOW-CONCENTRAION IMPURITY REGION OVERLAPS TaN

OF GATE ELECTRODE, 1304: CHANNEL REGION, 1305: DRAIN REGION, 1306:

5   CHANNEL REGION, 1307: REGION OVERLAPPING TaN OF GATE ELECTRODE,

1401: SOURCE REGION AND DRAIN REGION, 1402: CHANNEL REGION, 1403:

REGION OVERLAPPING TaN OF GATE ELECTRODE, 1501: CAP OXIDE FILM,

1502: INSULATING FILM, 1503: INSULATING FILM, 1504: WIRING, 1601:

NON-SINGLE CRYSTAL SEMICONDUCTOR FILM, 1602a: NON-SINGLE

10   CRSYTAL SEMICONDUCTOR FILM, 1602b: CRYSTALLINE SEMICONDUCTOR

FILM, 1603: FIRST INSULATING FILM, 1604: MICROPARTICLE OF SILICON

CRYSTAL, 1605: CONDUCTIVE FILM, 1606: FIRST CONDUCTIVE FILM, 1611:

SECOND CONDUCTIVE FILM, 1612: SECOND CONDUCTIVE FILM, 1613:

MASK PATTERN, 1621: GATE ELECTRODE, 1622: SECOND INSULATING

15   LAYER, 1623: FLOATING GATE ELECTRODE, 1631: SOURCE REGION, 1632:

DRAIN REGION, 1633: THIRD INSULATING FILM, 1634: FIRST INSULATING

FILM, 1635: SOURCE ELECTRODE, 1636: DRAIN ELECTRODE, 1701: PARTICLE

CONTAINING METAL ELEMENT, 1702: MICROPARTICLE CONTAINING

SILICON CRYSTAL, 1703: SUBSTRATE, 1711: PARTICLE CONTAINING METAL

20   ELEMENT, 1721: PARTICLE CONTAINING METAL ELEMENT, 1722: PARTICLE

CONTAINING METAL ELEMENT, 1723: PARTICLE CONTAINING METAL

ELEMENT, 1801: INSULATING SUBSTRATE, 1802: SEMICONDUCTOR FILM,

1803: HIGH-CONCENTRATION IMPURITY ELEMENT, 1804: CHANNEL

REGION, 1805: GATE INSULATING FILM, 1806: GATE ELECTRODE, 1808:

INSULATED REGION, 1901: CASE, 1902: SUPPORTING STAND, 1903: DISPLAY PORTION, 1904: SPEAKER PORTION, 1905: VIDEO INPUT TERMINAL, 1911: CASE, 1912: DISPLAY PORTION, 1913: KEYBOARD, 1914: EXTERNAL CONNECTION PORT, 1915: POINTING MOUSE, 1921: CASE, 1922: DISPLAY PORTION, 1923: OPERATION KEY, 1941: PASSPORT, 1942: RADIO FREQUENCY IC TAG, 1951: RADIO FREQUENCY IC TAG, 1952: READER, 1953: ANTENNA PORTION, 2001: BEAM SPOT, 2002: ENERGY DENSITY DISTRIBUTION, 2003: CENTRAL REGION OF BEAM SPOT, 2004: END PORTION OF BEAM SPOT, 2100: SEMICONDUCTOR FILM, 2101: SOURCE SIGNAL LINE, 2102: GATE SIGNAL LINE, 2103: CURRENT SUPPLYING LINE, 2104: SWITCHING TFT, 2105: DRIVER TFT, 2106: CAPACITOR, 2107: LIGHT-EMITTING ELEMENT, 2109: MICROCRYSTAL REGION, 2201: MICROCRYSTAL REGION, 2701: DISPLAY PANEL, 2702: PRINT SUBSTRATE, 2703: PIXEL PORTION, 2704: FIRST SCANNING LINE DRIVER CIRCUIT, 2705: SECOND SCANNING LINE DRIVER CIRCUIT, 2706: SIGNAL LINE DRIVER CIRCUIT, 2707: CONTROLLER, 2708: CENTRAL PROCESSING UNIT, 2709: MEMORY, 2710: POWER SUPPLY CIRCUIT, 2711: AUDIO PROCESSING CIRCUIT, 2712: SENDING/RECEIVING CIRCUIT, 2713: FLEXIBLE WIRING SUBSTRATE, 2714: INTERFACE (I/F) PORTION, 2715: ANTENNA PORT, 2716: VRAM, 2717: DRAM, 2718: FLASH MEMORY, 2719: INTERFACE, 2720: CONTROL SIGNAL GENERATING CIRCUIT, 2721: DECODER, 2722: RESISTOR, 2723: ARITHMETIC CIRCUIT, 2724:VRAM, 2725: INPUT MEANS, 2726: MICROPHONE, 2727: SPEAKER, 2728: ANTENNA